US00D785780S

(12) **United States Design Patent**
Scarbrough et al.

(10) **Patent No.: US D785,780 S**
(45) **Date of Patent: ** May 2, 2017**

---

(54) **RESPIRATORY FILTRATION MASK**

(71) Applicants: **Elizabeth Ann Scarbrough**, Ventura, CA (US); **Wendell Bryan Liljedahl**, Ventura, CA (US)

(72) Inventors: **Elizabeth Ann Scarbrough**, Ventura, CA (US); **Wendell Bryan Liljedahl**, Ventura, CA (US)

(**) Term: **14 Years**

(21) Appl. No.: **29/497,231**

(22) Filed: **Jul. 22, 2014**

(51) **LOC (10) Cl.** **29-02**

(52) **U.S. Cl.**
USPC **D24/110.1**

(58) **Field of Classification Search**
USPC D24/110–110.5, 127, 164
CPC A61M 16/0683; A61M 16/0605; A61M 16/0622; A61M 16/06; A61M 16/0616; A61M 16/0661; A61M 16/0633; A61M 16/0644; A61M 16/0816; A61M 16/08; A61M 16/0666; A61M 2210/0618
See application file for complete search history.

(56) **References Cited**

U.S. PATENT DOCUMENTS

D224,277 S *	7/1972	Venaleck	D24/110.1	
4,084,585 A *	4/1978	Venaleck	A41D 13/1161	128/206.13
D380,545 S *	7/1997	Nozaki	D24/110.1	
5,701,892 A	12/1997	Bledstein		
5,717,991 A *	2/1998	Nozaki	A41D 13/113	128/206.13
7,032,751 B2 *	4/2006	Bell	A41D 13/1161	128/206.19
7,762,257 B2 *	7/2010	Chiam	A41D 13/1161	128/206.12
2004/0078860 A1 *	4/2004	Bell	A41D 13/1161	2/9
2004/0121107 A1 *	6/2004	Bell	A41D 13/1161	428/43
2005/0172968 A1 *	8/2005	Hishida	A62B 23/025	128/206.19
2006/0201513 A1	9/2006	Chu		
2007/0044802 A1	3/2007	Horne		

(Continued)

Primary Examiner — Barbara Fox
Assistant Examiner — Lilyana Bekic
(74) *Attorney, Agent, or Firm* — Bruce E. Weir

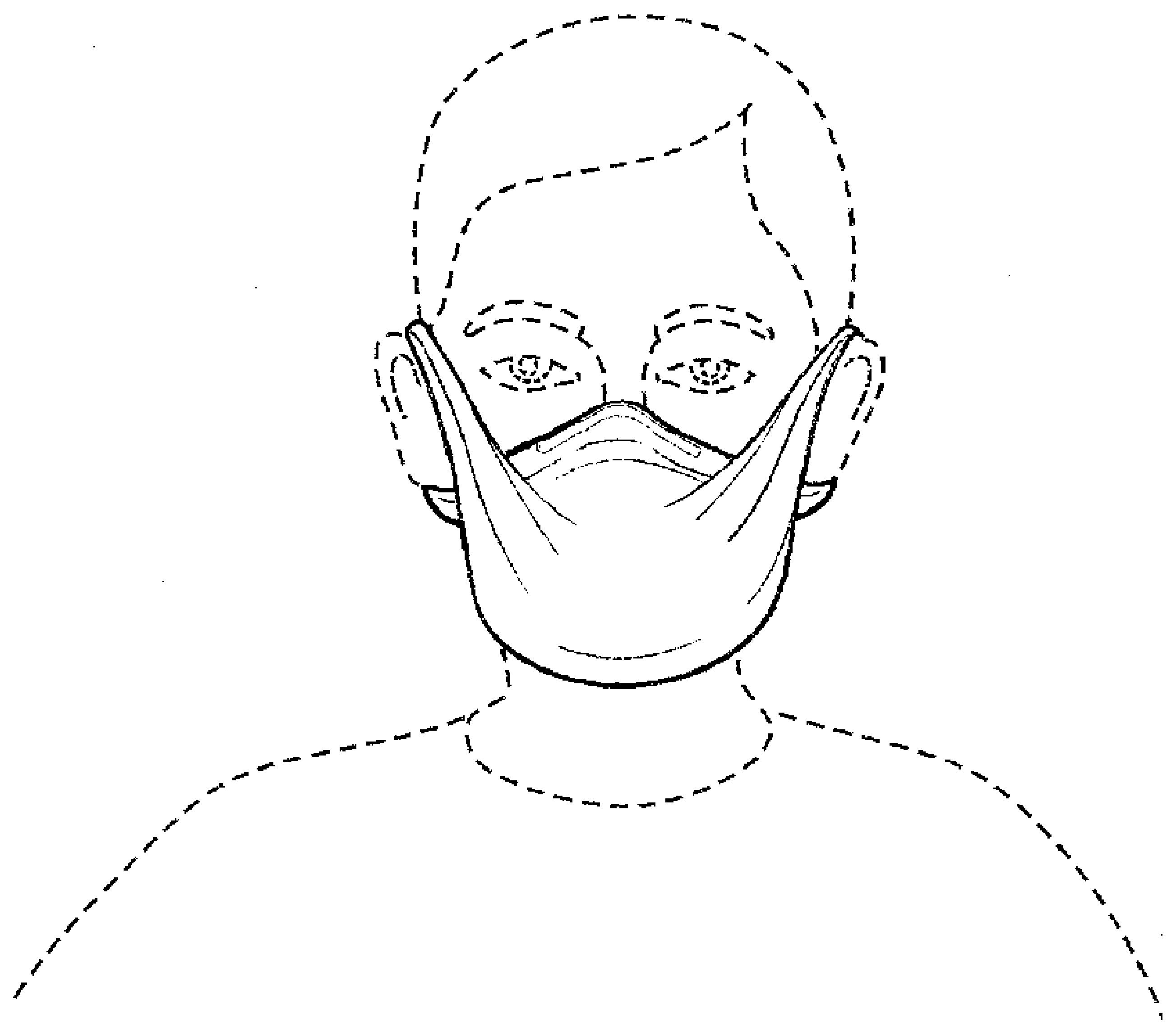
(57) **CLAIM**

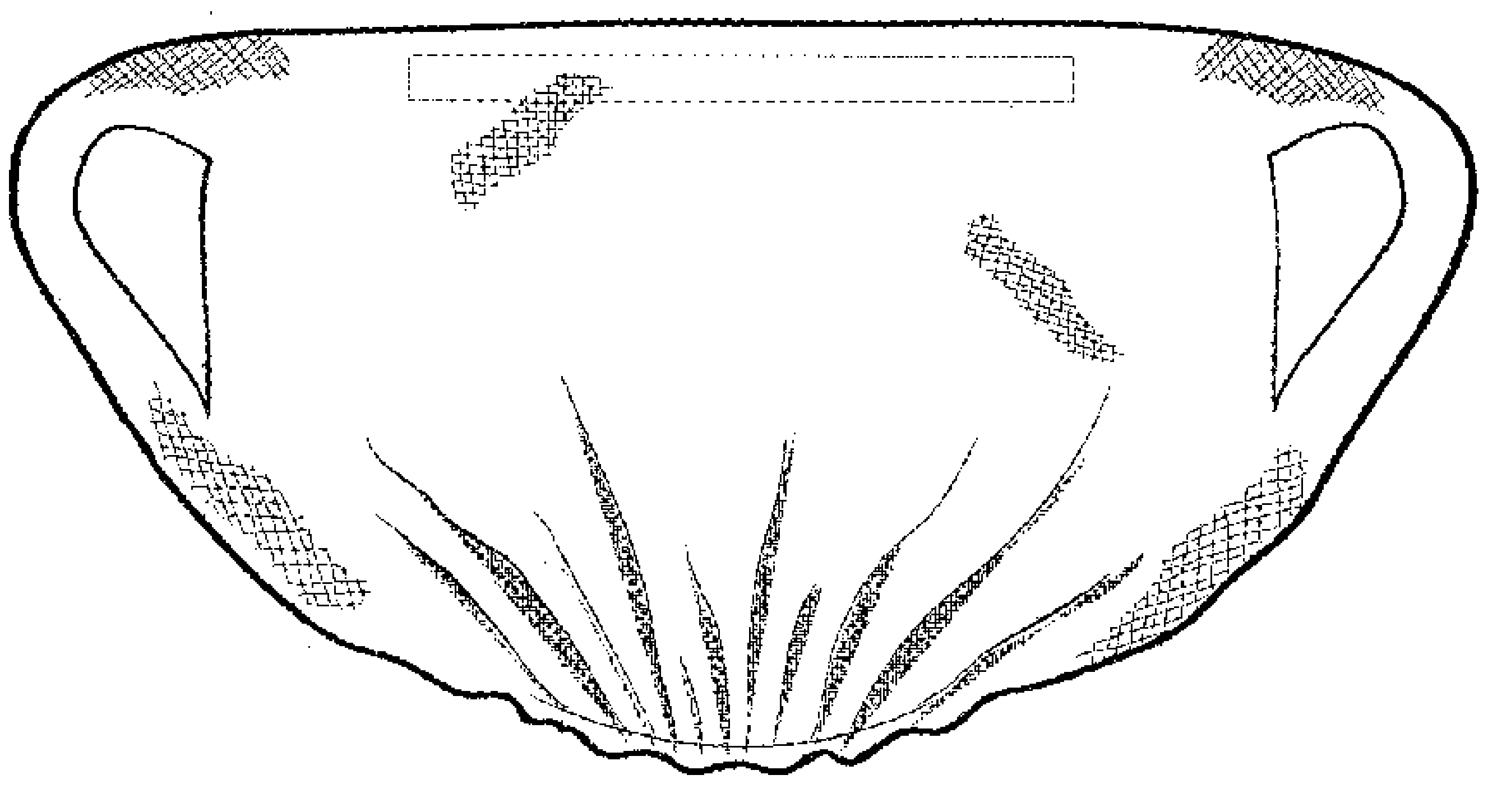
The ornamental design for a respiratory filtration mask, as shown and described.

DESCRIPTION

FIG. **1** is a front elevation view of a respiratory filtration mask showing our new design worn by a person.
FIG. **2** is a left side elevation view thereof.
FIG. **3** is a right side elevation view thereof.
FIG. **4** is a top, front perspective view thereof.
FIG. **5** is a bottom, front perspective view thereof.
FIG. **6** is an enlarged front elevation view of the respiratory filtration mask of FIG. **1** shown flattened.
FIG. **7** is a rear elevation view thereof.
FIG. **8** is a top plan view thereof.
FIG. **9** is a bottom plan view thereof.
FIG. **10** is a left side elevation view thereof; and,
FIG. **11** is a right side elevation view thereof.
The broken lines in FIGS. **1** through **5** showing a person wearing the respiratory filtration mask are illustrative of environmental structure only and form no part of the claimed design.
The stippled pattern in FIG. **7** is meant to represent a first fabric. The crosshatched pattern in FIGS. **6**, **7**, **10** and **11**, although shown intermittently, is meant to represent a second fabric and is understood to be uniformly distributed over the surfaces of the claimed design not covered by the stippled pattern.

1 Claim, 5 Drawing Sheets





(56) **References Cited**

U.S. PATENT DOCUMENTS

2008/0105261	A1	5/2008	Harold		
2010/0307503	A1*	12/2010	Iwamoto	A62B 18/025	128/205.29
2012/0180800	A1*	7/2012	Shibata	A41D 13/113	128/863
2012/0318273	A1*	12/2012	Tsuei	A62B 23/025	128/206.19
2014/0224261	A1*	8/2014	Tsuei	A41D 13/1115	128/863
2014/0261428	A1*	9/2014	Chen	A62B 18/006	128/205.12
2015/0173436	A1*	6/2015	Tsuei	A62B 7/10	2/424
2016/0113336	A1*	4/2016	Shibata	A41D 13/113	128/863

* cited by examiner

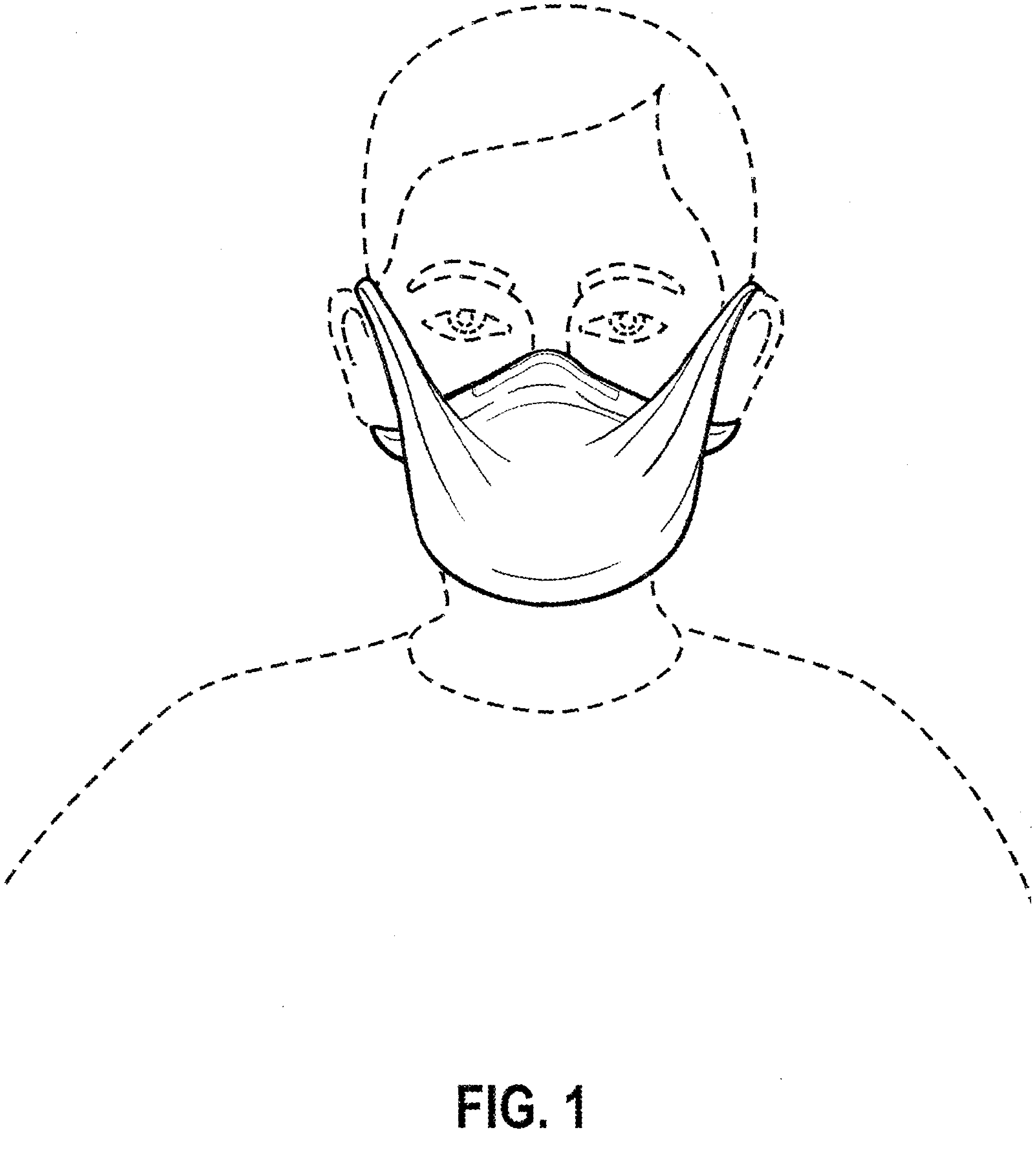


FIG. 1

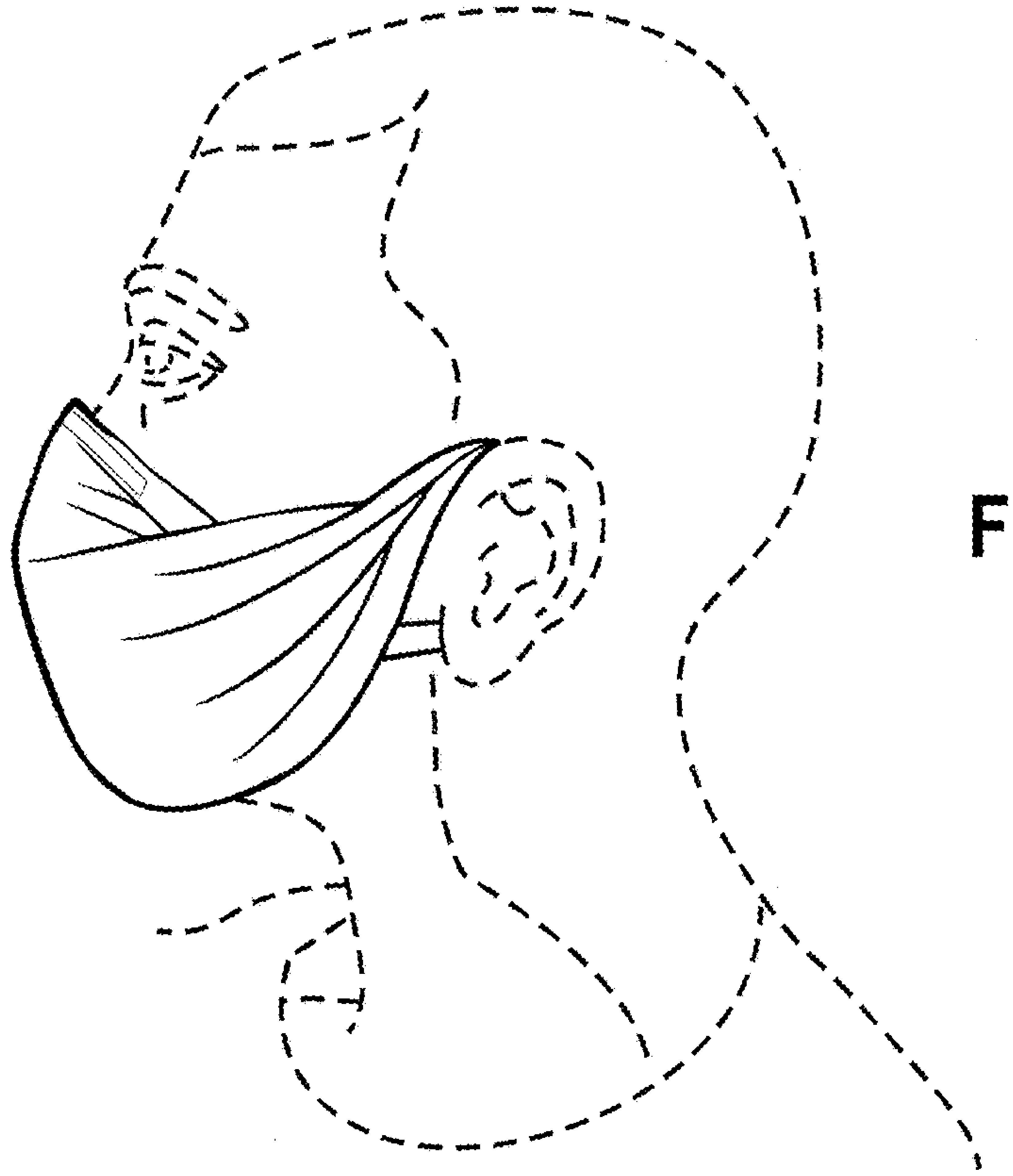


FIG. 2

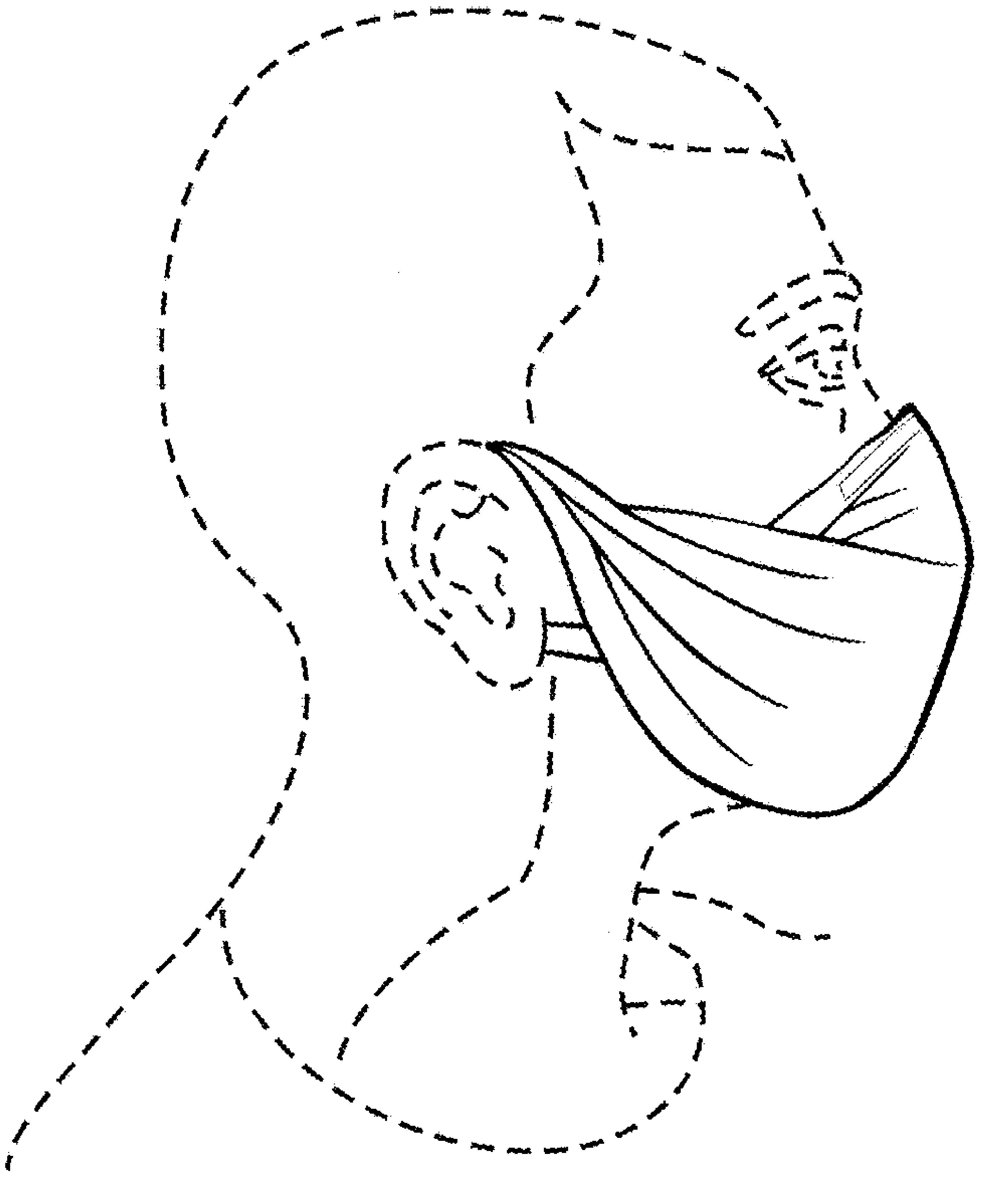
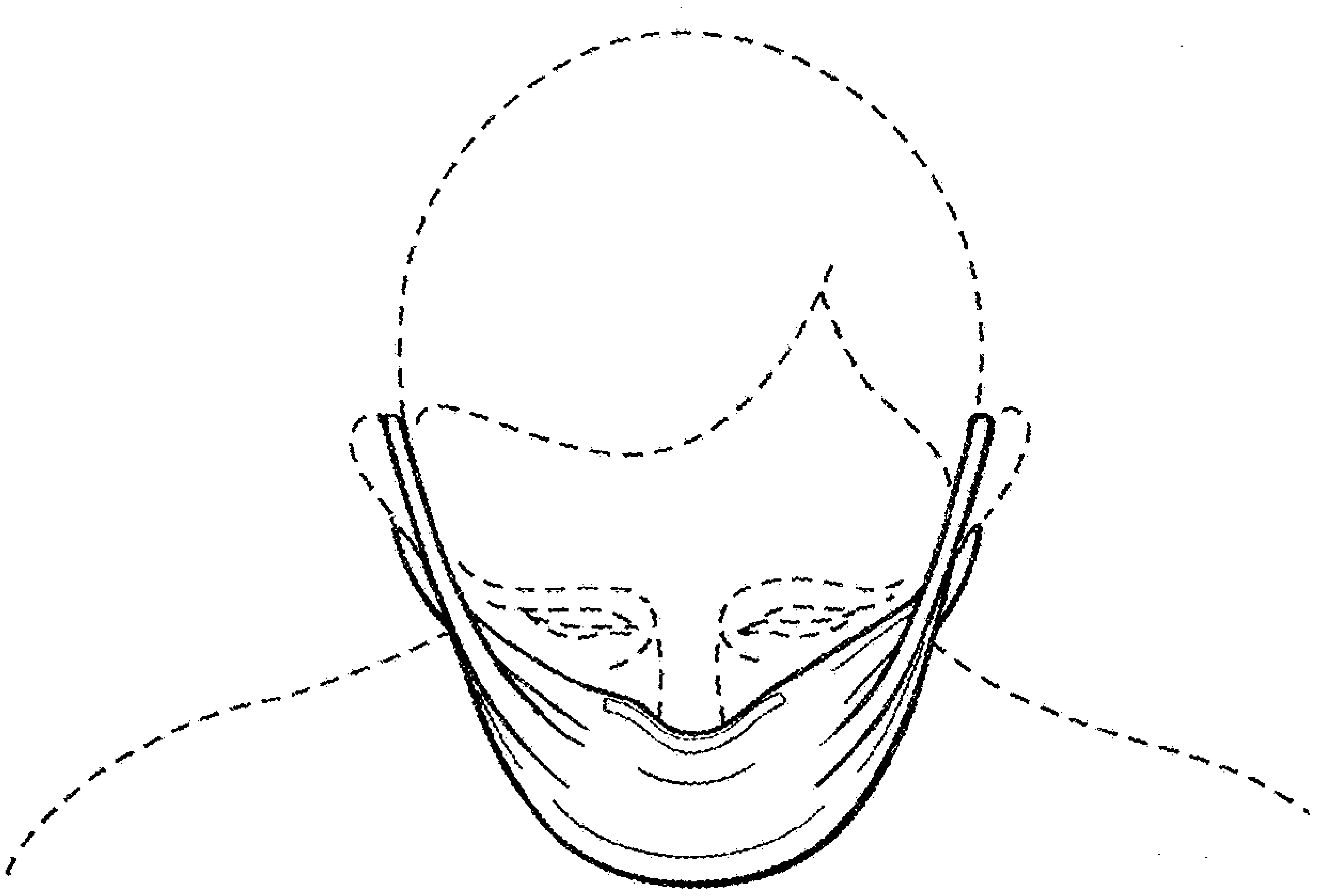


FIG. 3

FIG. 4



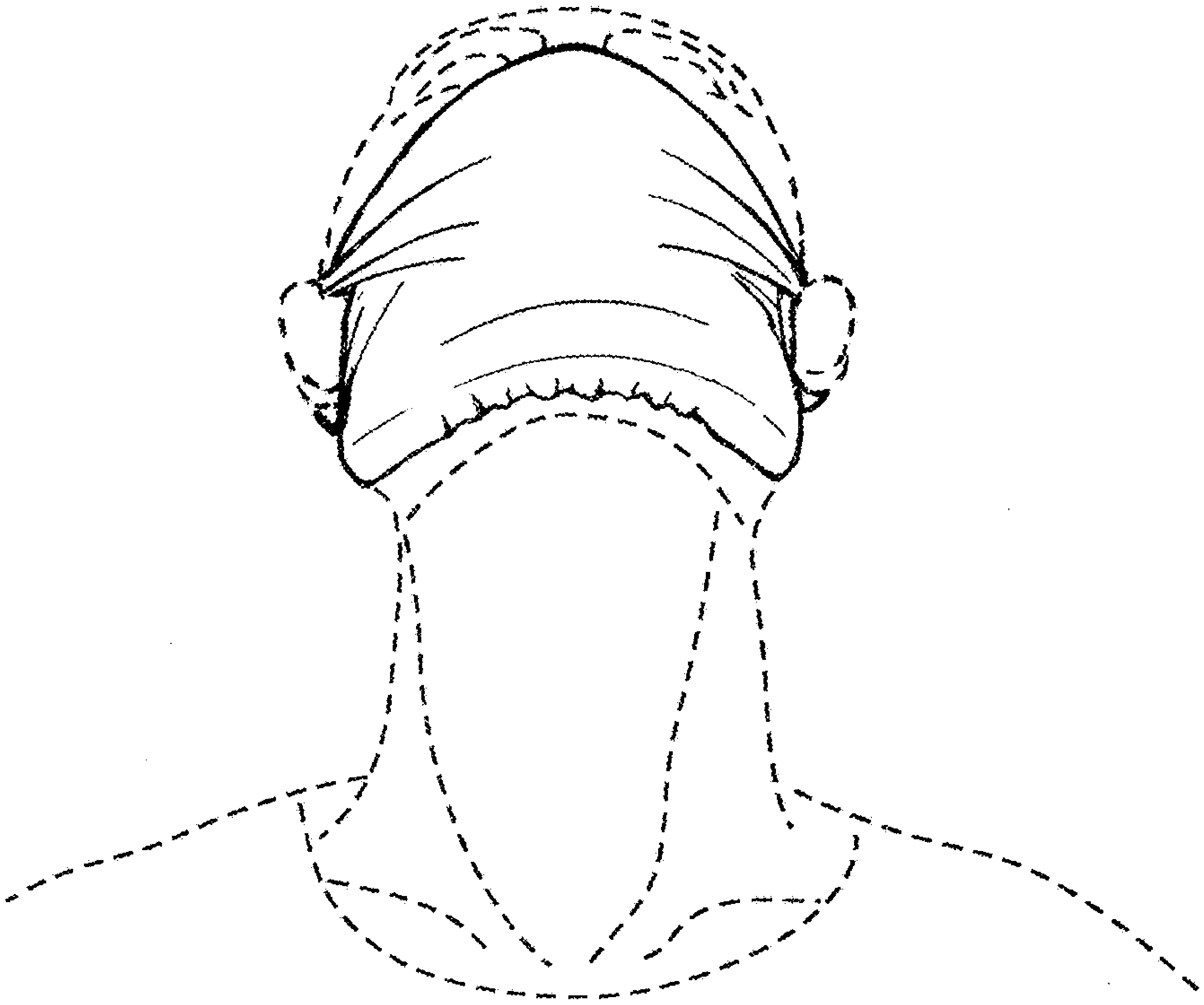


FIG. 5

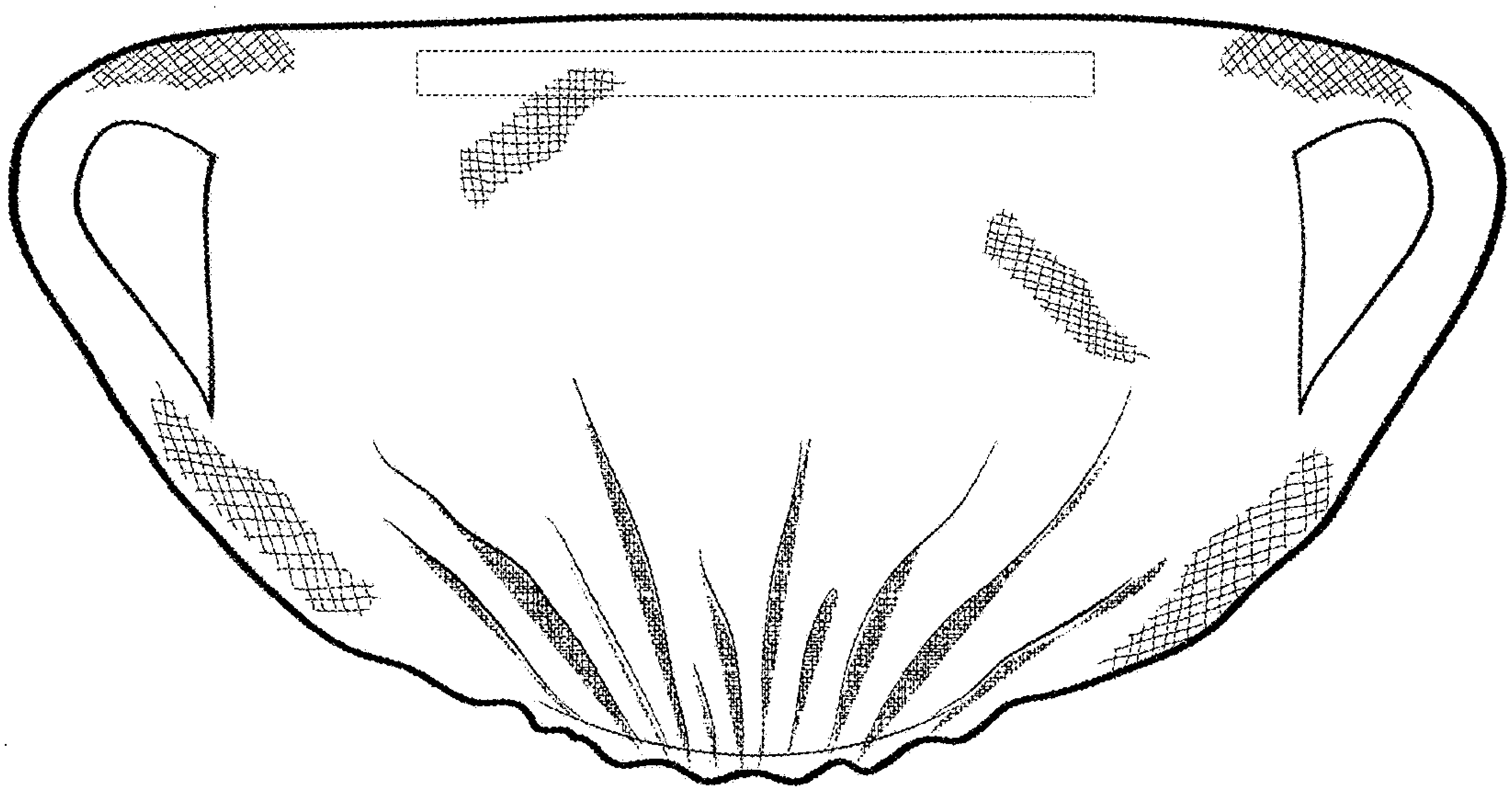


FIG. 6

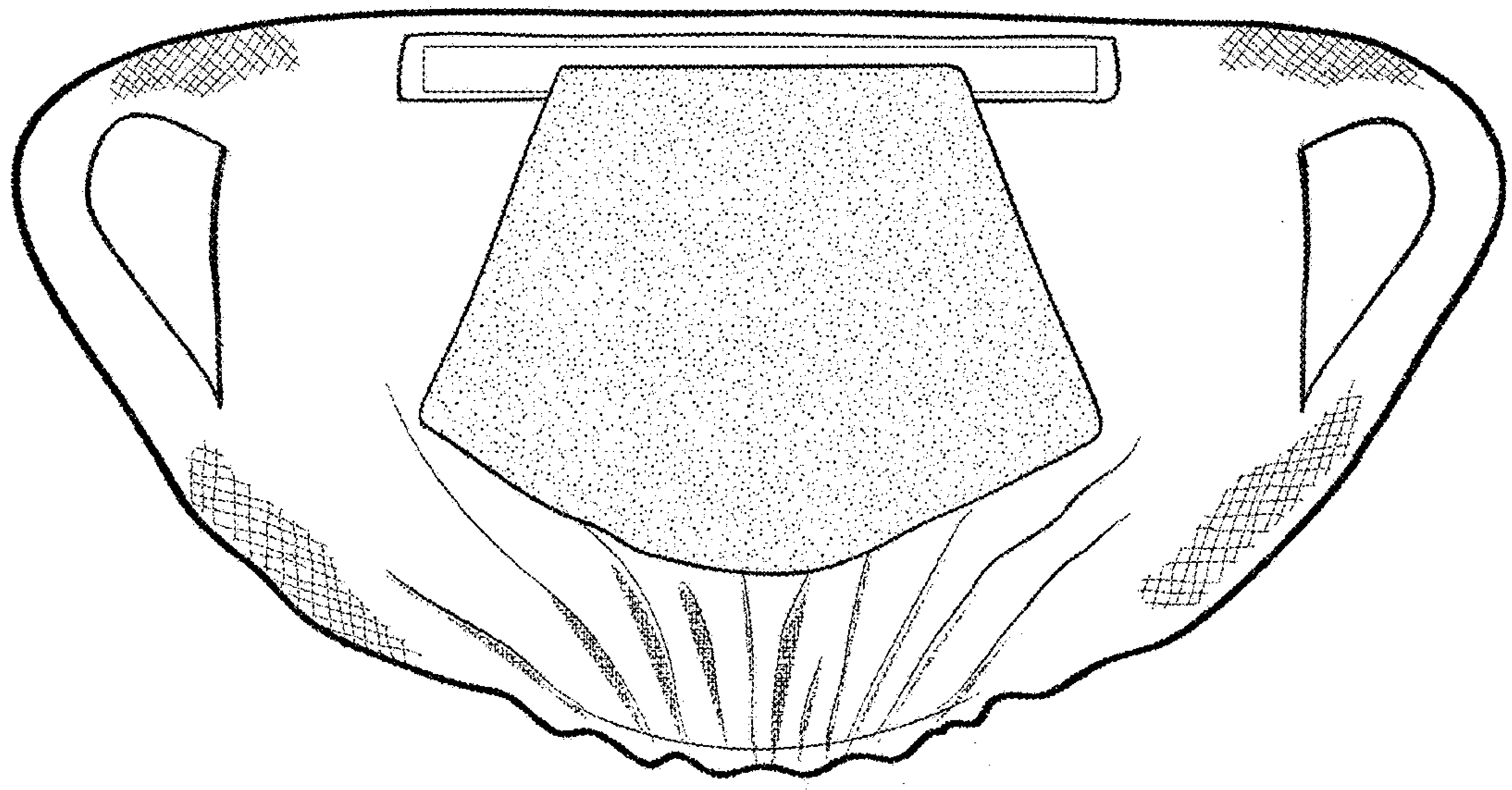


FIG. 7

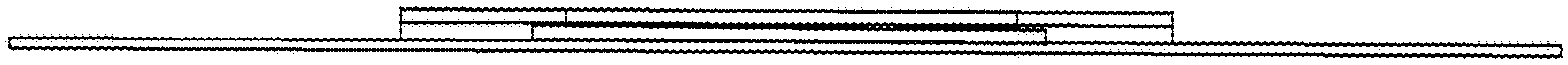


FIG. 8

FIG. 9

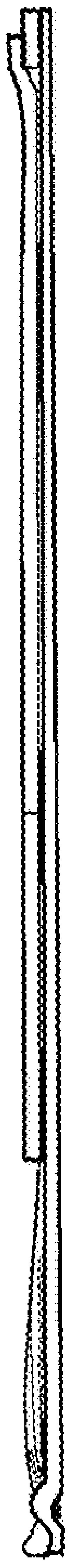


FIG. 10

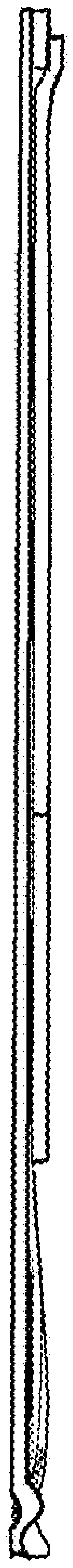


FIG. 11